Form	PTO	D-1449	,				F COMMERCE MARK OFFICE	ATTY. DOCKET NO. MI22-2497			SERIAL NO. 10/776,553			
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)								APPLICANT Weimin Li et al.						
			<u>. </u>					FILING DAT		GROUP 1755				
	U.S. PATENT DOCUMENTS													
*Exam Initi				Document Number	Date		Name	Class	Sub- class		Filing If Appro			
		. 🔼	A	5,994,217	11-1999	Ng			F					
\prod			в	5,991,217	11-1999	Tavrov	w et al.							
			ıc	5,985,519	11-1999	Kakam	Kakamu et al.			F	-			
		A	9	5,747,388	05-1998	Küster	Küsters et al.			F				
		_^	/E	5,639,687	06-1997	Romar	n et al.			F				
		1	VF	5,498,555	03-1998	Lin	Lin			F				
		A	G	6,498,084 B 2	12-2002	Bergen	mont			F	-			
		TA	Ŧ	5,036,383	07-1991	Mori	Mori			F				
			A.	6,638,875	10-2003	Han et	t al.			F	-			
		1	2	6,720,247	04-2004	. Kirkpa	Kirkpatrick# et al.			F	-			
		A	ĸ	6,723,631	04-2004	Noguc	Noguchi et al.			F	_			
			u.	5,593,741	01-1997	Ikeda	lkeda			Ę				
	_		_		F	OREIGN P	PATENT DOCUMEN	NTS	·	-		1		
		İ		Document Yumber	Date ·		Country		Ctass	Su 88	ıbcla	Trans	station No	
B	B		Ī	471185 A2	02/92	EPO	EPO			E		168	NU	
C			0 464515 A3		01/92	EPO				匚				
3	3		Ļ۵	771888 A1	05/97	EPO			 	二				
0		AP 08-213386A			08-1996	Japan				上	· .		<u> </u>	
				OTHER	REFERENCES	3 (including	ng Author, Title, Dat	ie, Pertinent Pag	es, Etc.)					
C	\dashv	AR		Wolf, Silicon	Processing	, for the	VLSI Era, Vol.	. 2: Process	Integration,	.· o	1990	, pp. 189	-190.	
C.		AS Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).										θ,		
Heavens, O.S., "Optical Properties of Thin Solid Films", pp								d Films", pp.	48-49.		·			
EXAMIN	ÆR	R	_				DATE CONSIDERED 8/13/05							
*EXAM	NER:	: Initia	i II r	reference considered,	, whether or n	not citation	is in conformanc	a with MPEP 6	09; Draw Env	e thr	ough c	Ration if no	a in	

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